

<b>Notice of References Cited</b>	Application/Control No. 10/732,931		Applicant(s)/Patent Under Reexamination KIM ET AL.	
	Examiner Patricia A. George		Art Unit 1765	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,190,999	02-2001	Hung et al.	438/424
*	B	US-5,716,890	02-1998	Yao, Liang-Gi	438/624
*	C	US-6,117,698	09-2000	Atobe et al.	438/21
*	D	US-6,531,377	03-2003	Knorr et al.	438/435
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Dobins (High Density Plasma Deposition of SiO <sub>2</sub> ; <a href="http://www.enigmatic-consulting.com/semiconductor_processing/CVD_Fundamentals/films/HDP_SiO2.html">http://www.enigmatic-consulting.com/semiconductor_processing/CVD_Fundamentals/films/HDP_SiO2.html</a> ) web page created March 2005
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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